## **ELECTRONIC INFORMATION DISCLOSURE STATEMENT**

## Electronic Version v18

Stylesheet Version v18.0

Title of Invention

PROCESS OPTIONS OF FORMING SILICIDED METAL GATES FOR ADVANCED CMOS DEVICES

**Application Number:** 

Confirmation Number:

First Named Applicant:

Ricky Amos

Attorney Docket Number:

FIS920020157US1

Art Unit:

Examiner:

Search string:

( 5723893 or 6147388 or 6180501 or 6277719 or 6465312 ).pn

## **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

inj	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
16	1	5723893	1998-03-03	YU, ET AL.			
$\Box$	2	6147388	2000-11-14	MA, ET AL.			
	3	6180501	2001-01-30	PEY, ET AL.			
	4	6277719	2001-08-21	CHERN, ET AL.			
MA	5	6465312	2002-10-15	YU			
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